In the Specification:

Please insert before the first paragraph of the application:

This application is the national stage application of international application number PCT/DE2003/01956, filed on June 12, 2003, which claims the benefit of priority to German Patent Application DE 10230697.4, filed on July 8, 2002, incorporated herein by reference.

Please delete the paragraph on page 2, lines 14-16.

Please rewrite the paragraph on page 7, lines 13-28 as follows:

The main capacitor 12 and the disconnectable capacitors 46-14 are electrically connected in parallel by interconnects 32 between the bottom electrodes 18, 20 and by interconnects 34 between the electrodes 24, 26 remote from the substrate. As seen geometrically, however, the disconnectable capacitors 14 are arranged in a row one behind the other. The interconnects 32 and 34 are situated in an upper metallization layer. A cutout 36 and 38 in an insulating material (not illustrated) which covers the interconnects 32 and 34 respectively leads to each interconnect 32 and 34. Through the cutouts 36 and 38, during a correction of the capacitance of the main capacitor 12, regions 40 and 42 of an interconnect 32 and 34, respectively, can be vaporized with the aid of a laser beam, thereby producing an interruption.

Please rewrite the paragraph on page 16, line 37 as follows:

 $\Delta C = \Delta Aeff / \Delta Aeff$ or $\Delta C = \Delta Deff / Deff$